

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|--|---|---------------------|
| 1 | 5295 | (250/492.2,504R,492.1).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 00:57 |
| 2 | 3764 | (extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 00:58 |
| 3 | 2517 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:45 |
| 4 | 494 | ((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:46 |
| 5 | 480 | ((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:01 |
| 6 | 380 | (((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:01 |
| 7 | 111 | ((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:01 |
| 8 | 74 | ((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode) and collect\$8 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:02 |
| 9 | 12 | ((((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode) and collect\$8) and (collect\$4 with (by-product\$4 or pollut\$5 or contamin\$4 or debris)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:47 |
| 10 | 222 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:45 |

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|----|-----|--|---|---------------------|
| 11 | 193 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)) and (mask or reticle or (pattern\$4 near1 structure)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:46 |
| 12 | 79 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)) and (mask or reticle or (pattern\$4 near1 structure)) and (by-product\$4 or pollut\$5 or contamin\$4 or debris) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:46 |
| 13 | 4 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)) and (mask or reticle or (pattern\$4 near1 structure)) and (by-product\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 01:46 |
| 14 | 36 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure)) and (by-product\$4 or pollut\$5 or contamin\$4 or debris) and (substrate or wafer or sample) and project\$5) and electrode) and collect\$8) and (plasma with (by-product\$4 or pollut\$5 or contamin\$4 or debris)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 02:28 |
| 15 | 14 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure)) and (by-product\$4 or pollut\$5 or contamin\$4 or debris) and (substrate or wafer or sample) and project\$5) and electrode) and collect\$8) and (plasma with (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and ((250/492.2,504R,492.1).CCLS.) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 02:29 |
| 16 | 3 | ((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure)) and (by-product\$4 or pollut\$5 or contamin\$4 or debris) and (substrate or wafer or sample) and project\$5) and electrode) and collect\$8) and (plasma with (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (particle with mov\$6) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/09/26 02:29 |